Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[WeD1] LIthography Process

Session Date	November 12 (Wed.), 2025
Session Time	09:00-10:40
Session Room	Room D (Sydney Room, 2F)
Session Chair	Dr. Jeong-Ho Yeo (Applied Materials, Korea)

[WeD1-1] [Invited] **09:00-09:30**

Journey to the Future: Low & High NA EUV Lithography for Next Generation Logic Devices

Jong-Hwa Baek (Samsung Electronics Co., Ltd., Korea)

[WeD1-2] [Invited] **09:30-10:00**

EUV Mask Technology: Evolution and Future Outlook

Chan-Uk Jeon (Tekscend Photomask Corp., Japan)

[WeD1-3] [Invited] **10:00-10:20**

SEM Overlay Target Optimization for NZO Improvement by Measuring Device Like Target Using E-Beam Simulation

You Jin Kim, Jeong Ho Yeo, Youngje Um (Applied Materials Korea, Korea), Jenny Perry, Noam Oved, Uri Smolyan, Tal Itzkovich, Michael Shifrin (Applied Materials Israel, Israel), Young Jin Cha, Baek Jun Kim (Applied Materials Korea, Korea), Ikjun Jang, Il Hwan Kim, Byounghoon Kim, Sungbin Jeon, Muyoung Lee, Hyunju Song, Myeongcheol Go, Narim Noh, Hachul Shin, Sangsu Jeong, Eunho Choi, Jinhong Park, and Changmin Park (Samsung Electronics Co., Ltd., Korea)

[WeD1-4] [Invited] **10:20-10:40**

Development of EUV Pellicles Supporting High EUV Power

Prashant Purwar, Dongyeong Yoo, Munsu Choi, Arim Kim, Chulkyun Park, Sangmin Jeong, Byoung Hoon Seung, and Juhee Hong (S&S TECH., Korea)